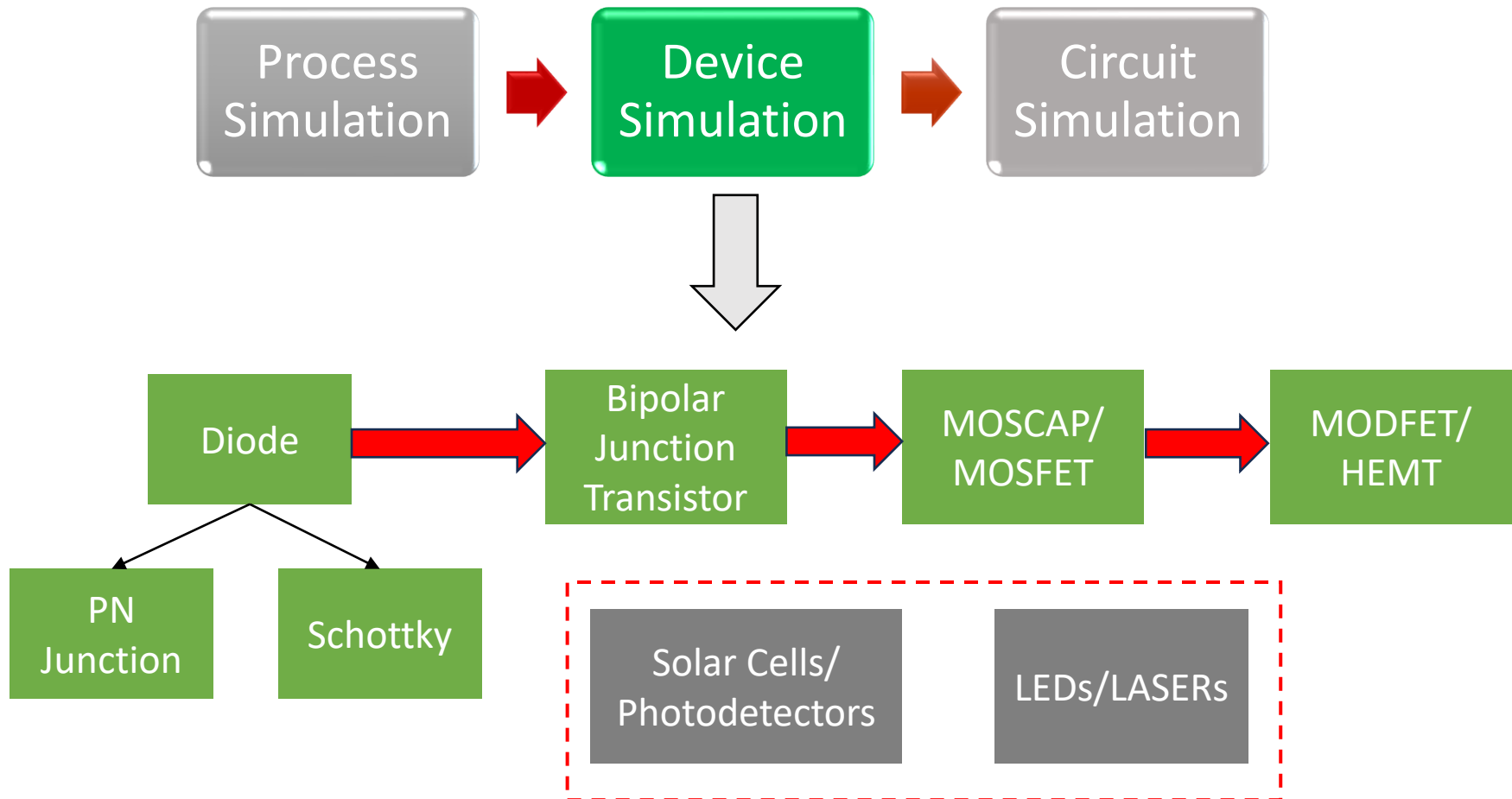


# Introduction to SILVACO ATLAS TCAD Tool

Course ECE 445  
Swarnav Mukhopadhyay

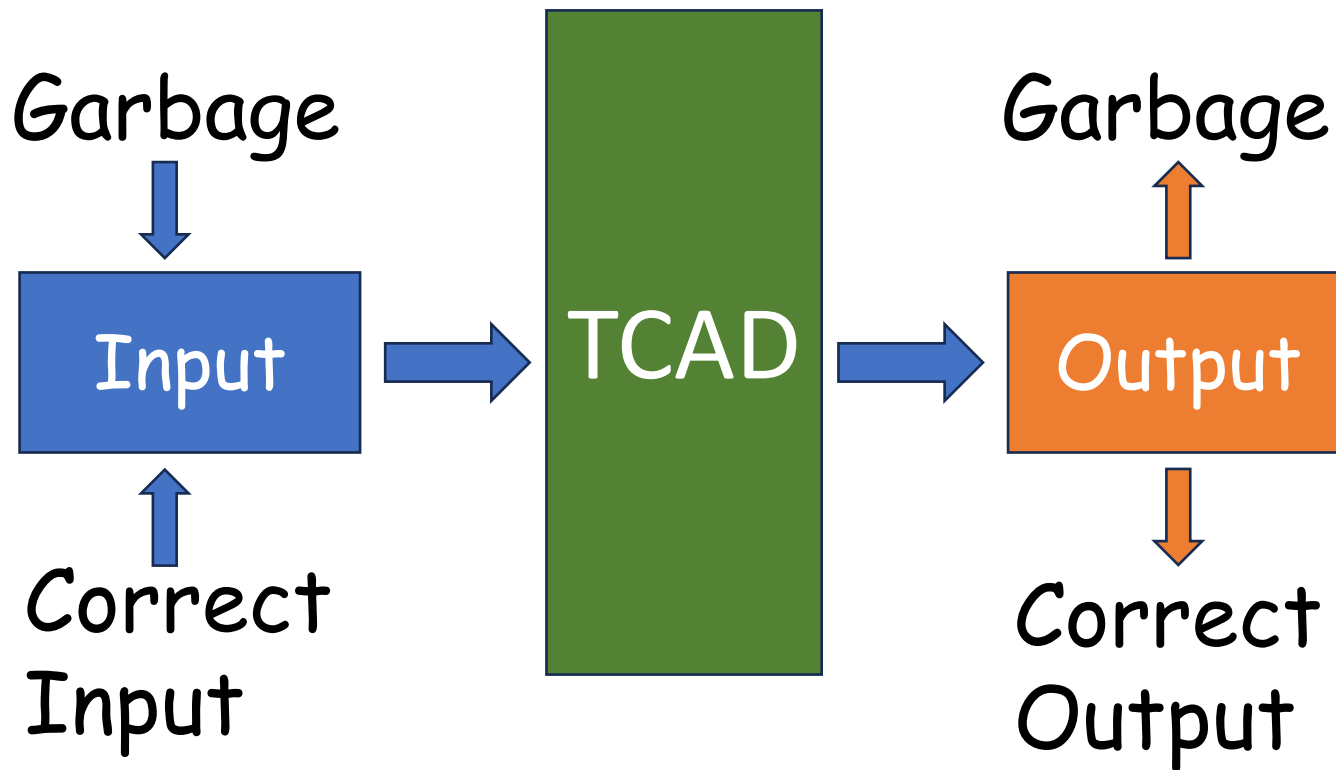
# What is TCAD??

Technology Computer-Aided Design



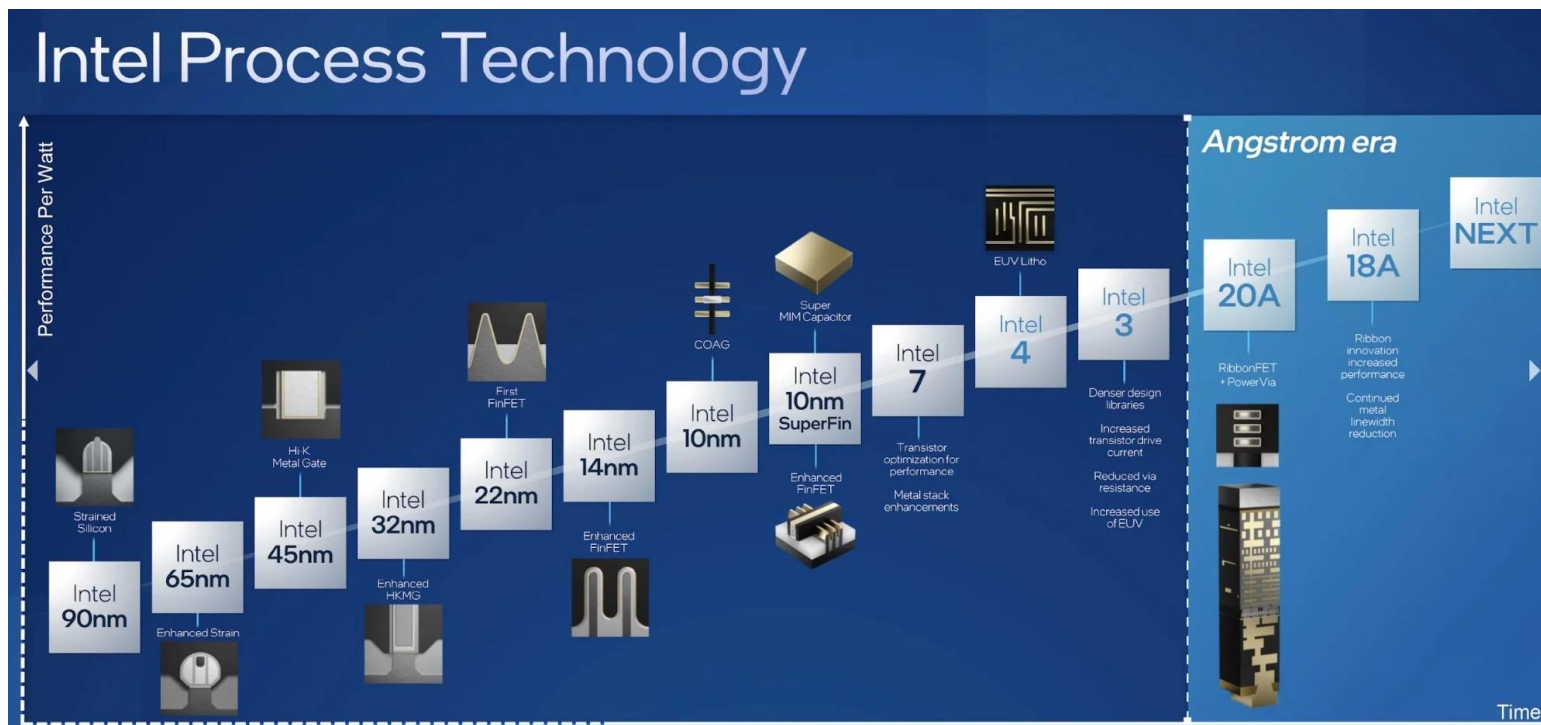
# Do We Trust TCAD??

**NO!! Always Verify Twice!**



# What Can we do with TCAD?

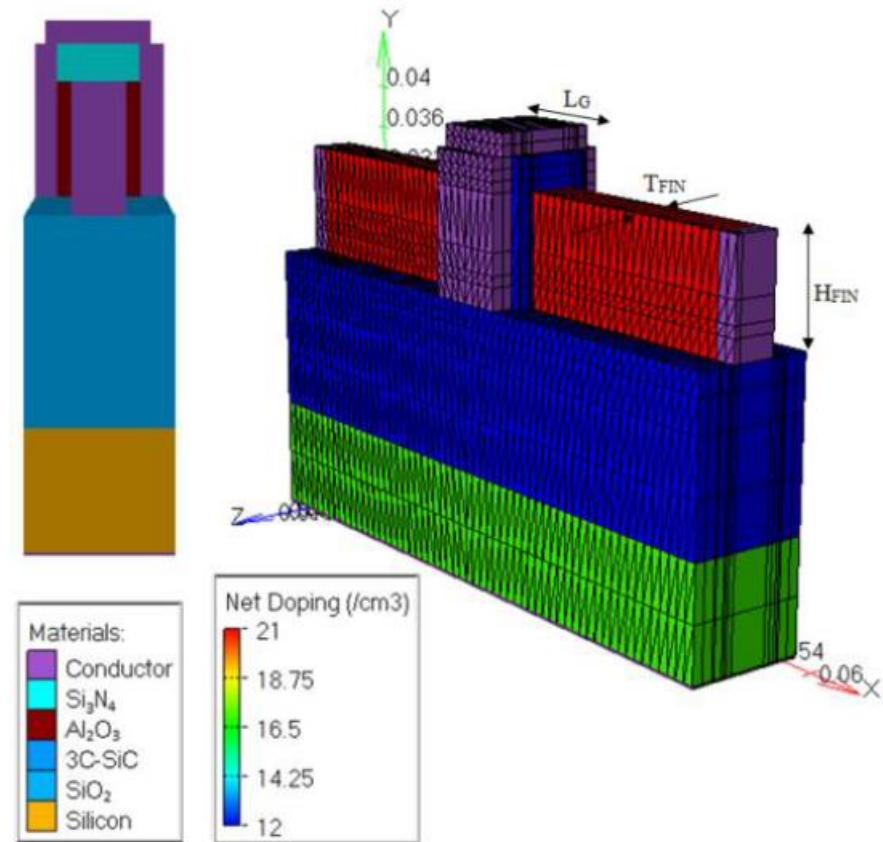
## SIMULATE ANY DEVICE!



Let's Get Started with TCAD!

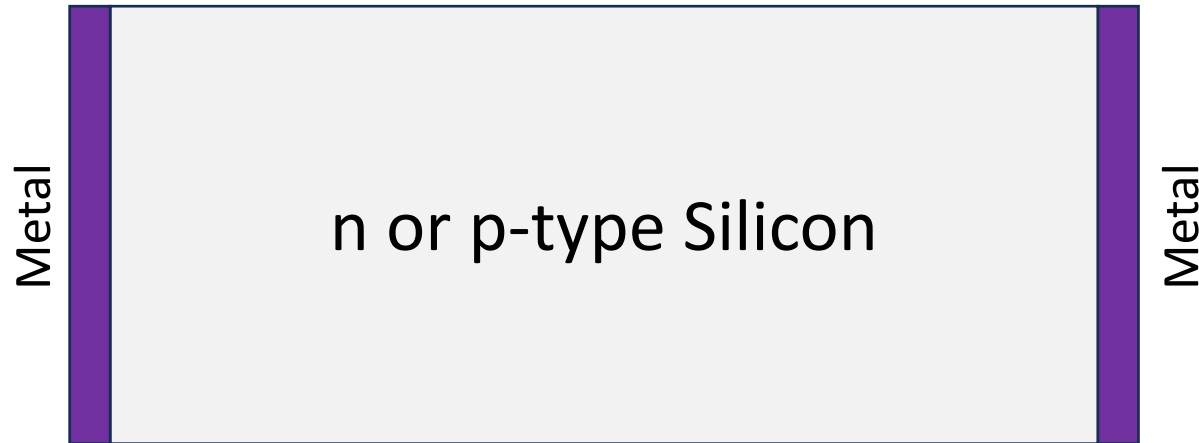
# Basics of TCAD

Group		Statements
1. Structure Specification	————	MESH REGION ELECTRODE DOPING
2. Material Models Specification	————	MATERIAL MODELS CONTACT INTERFACE
3. Numerical Method Selection	————	METHOD
4. Solution Specification	————	LOG SOLVE LOAD SAVE
5. Results Analysis	————	EXTRACT TONYLOT



# Defining the Structure

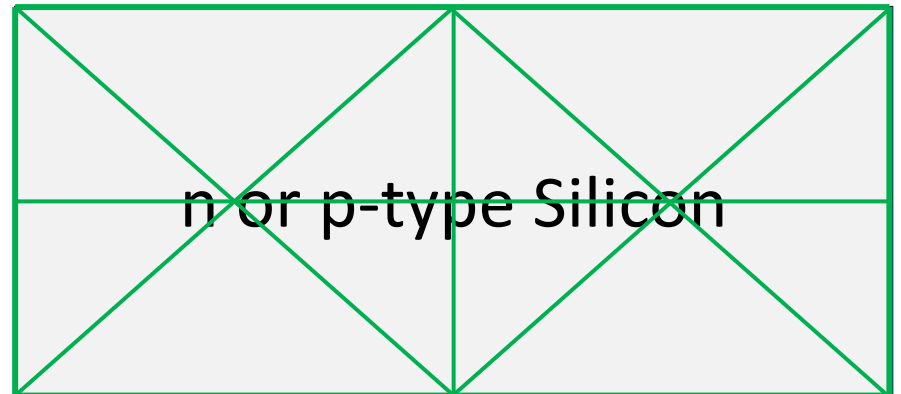
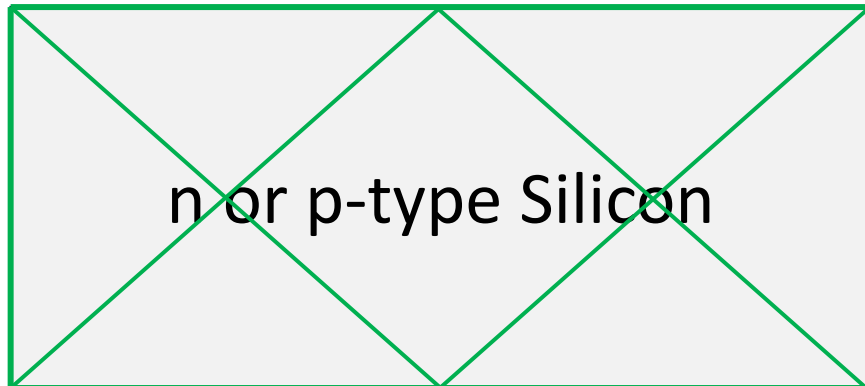
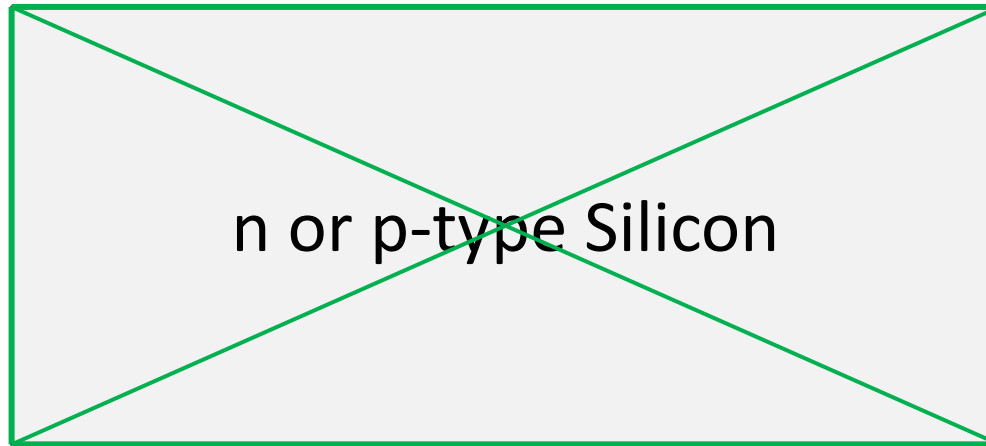
Mesh Design/ Digitization of the simulation area



We want to simulate different properties (Current densities, Electric field, doping profile, band diagram etc.) of this resistor

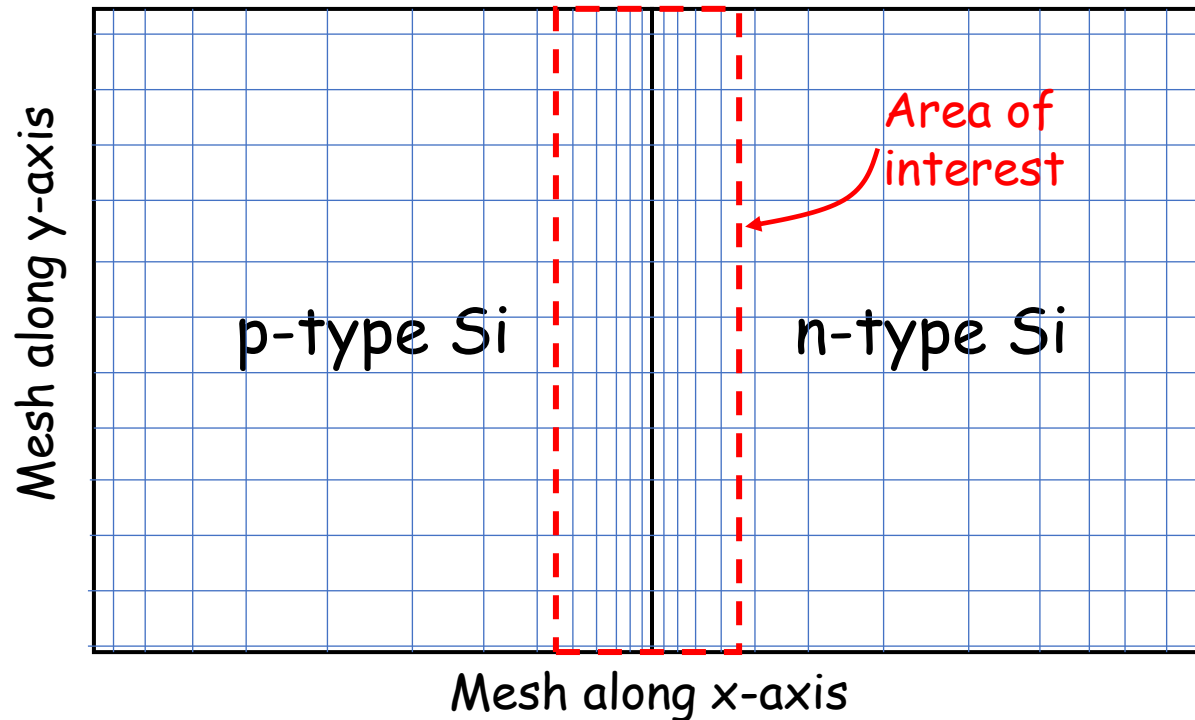
# How to digitize the device?

We can create different densities of meshing





# How to design a mesh?



Denser at the junction (Where electric-field changes) and coarse at the middle

```
MESH SPACE.MULT=<VALUE>
```

This is followed by a series of X.MESH and Y.MESH statements.

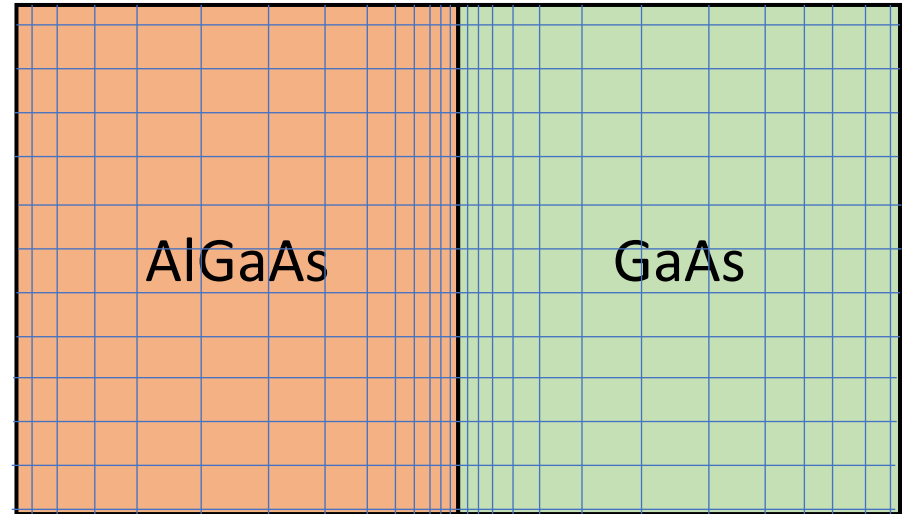
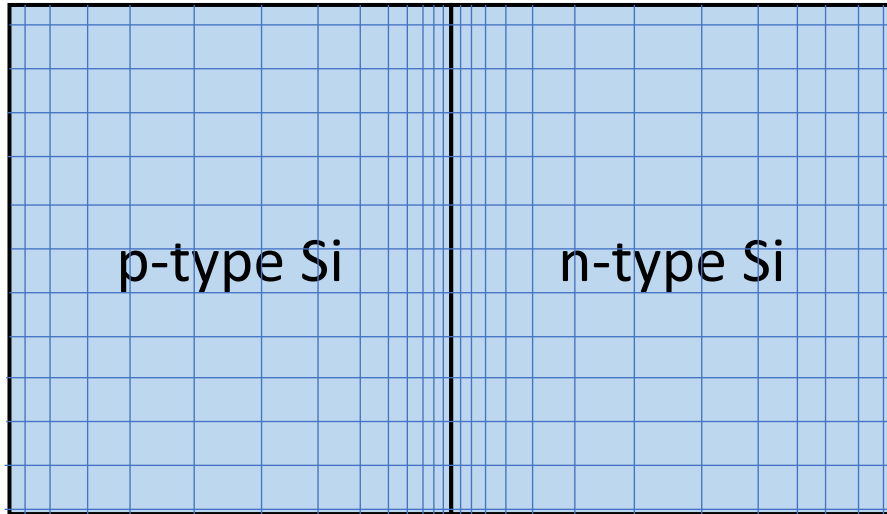
```
X.MESH LOCATION=<VALUE> SPACING=<VALUE>
```

```
.
```

```
Y.MESH LOCATION=<VALUE> SPACING=<VALUE>
```

Some useful features:  
Auto mesh, Regrid etc.

# Defining a Region



You can define different materials in different regions.  
Regions can't exceed the area of the mesh.

```
REGION number=<integer> <material_type> <position parameters>
```

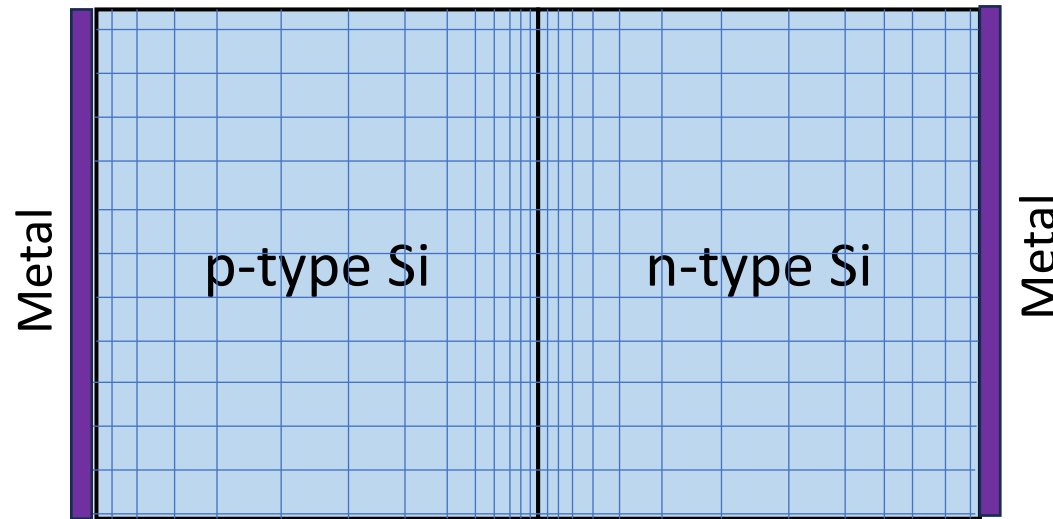
Position parameter: x.min=, x.max=, y.min=, y.max=

```
REGION NUM=1 Y.MAX=0 MATERIAL=OXIDE
```

```
REGION NUM=2 Y.MIN=0 MATERIAL=SILICON
```

For defining composition of a material use x.comp= , y.comp=

# Defining a Electrode/Contact



You can define different materials in different regions.  
Regions can't exceed the area of the mesh.

```
ELECTRODE NAME=ANODE X.MIN=0.5 X.MAX=1.0
```

By default the contacts are ohmic in nature

For ohmic contact there would be no electric field present between metal and semiconductor

# Defining a Doping

Uniform Doping  
profile of  $x/\text{cm}^3$

Doping density  
Gaussian Doping of  
 $x/\text{cm}^3$

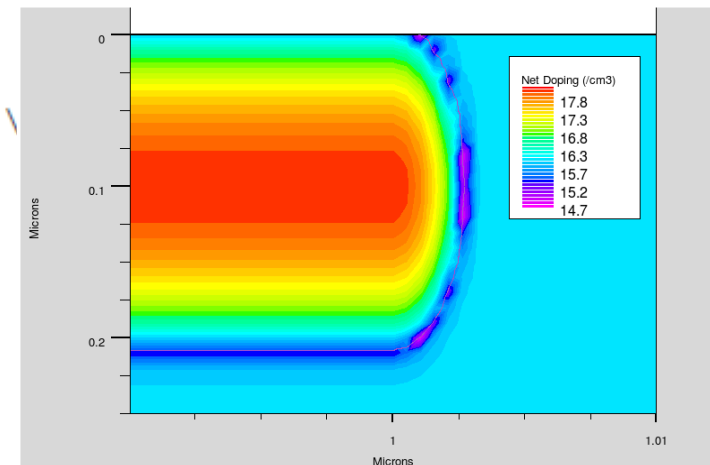
Doping density  
Gaussian Doping of  
 $x/\text{cm}^3$

Doping of specific type, concentration, profile, position can be defined

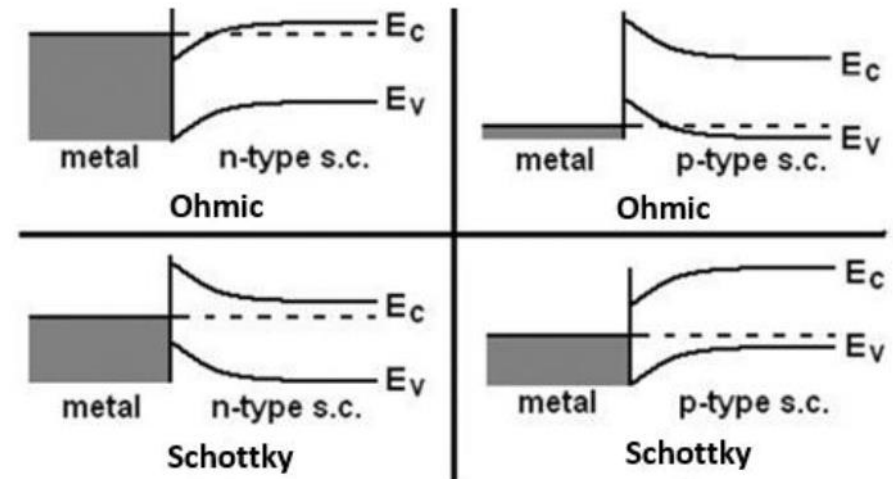
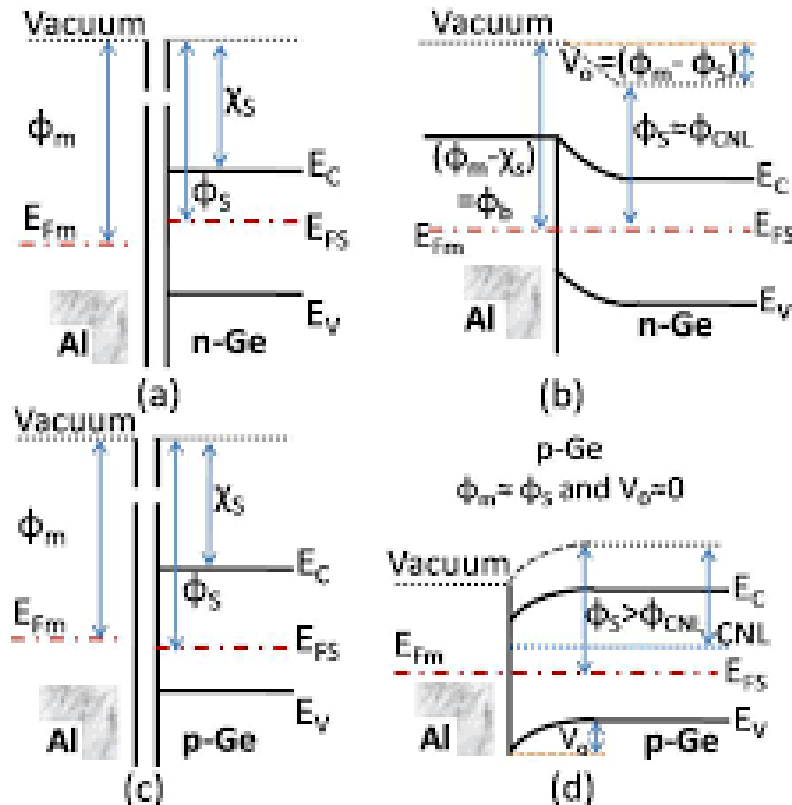
`DOPING <distribution type> <dopant type> <position parameters>`

```
DOPING UNIFORM CONCENTRATION=1E16 N.TYPE REGION=1
DOPING GAUSSIAN CONCENTRATION=1E18 CHARACTERISTIC=0.05 P.TYPE \
X.LEFT=0.0 X.RIGHT=1.0 PEAK=0.1
```

Commonly used doping  
profiles uniform and gaussian



# Defining a Contact Property



Defining a metal workfunction changes its property from ohmic to schottky

CONTACT NAME=gate WORKFUNCTION=4.8

By default the contacts are voltage controlled, you can change it to current controlled if you want to

CONTACT NAME=drain CURRENT

# How to define material properties?

## For Defining basic material properties:

1. Name of material
2. Type of material: Semiconductor, Insulator, Conductor
3. Bandgap
4. Band offsets between two materials
5. Affinity
6. Permittivity
7. Density of states
8. Mobility and/or effective mass
9. Ionization property ( $E_C - E_D$ ) or ( $E_A - E_V$ )
10. Thermal property
11. Transport property
12. Optical property

<https://www.ioffe.ru/SVA/NSM/Semicond/>

[https://www.tf.unikiel.de/matwis/amat/semitech\\_en/index.html](https://www.tf.unikiel.de/matwis/amat/semitech_en/index.html)

# What are different models?

Models are basically different physical phenomena that we want to use for obtaining certain output after the simulation

## Physical Models:

### 1. Carrier Statistics

- I. Fermi-Dirac
- II. Boltzmann
- III. Schrodinger
- IV. K.P

### 2. Transport properties

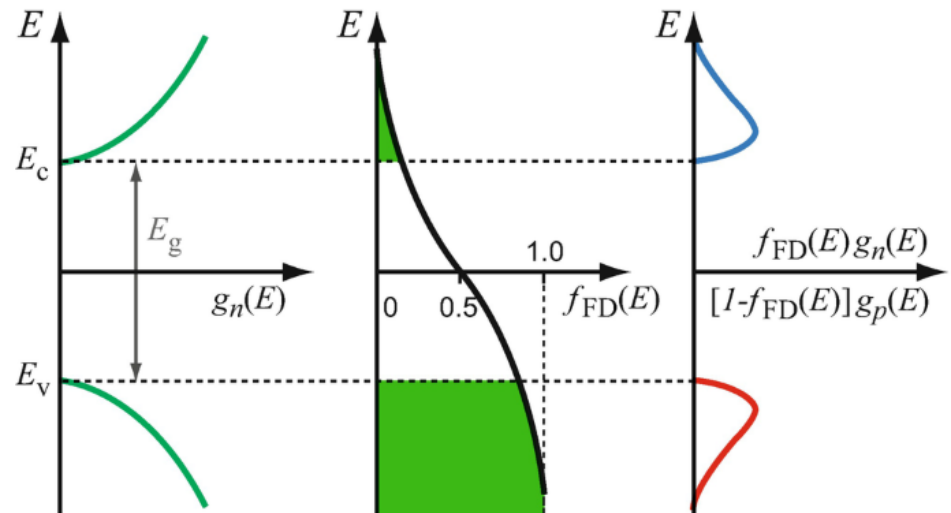
- I. Drift-diffusion
- II. Thermionic emission
- III. Field Emission
- IV. Tunneling

### 3. Mobility Models

### 4. Recombination models

### 5. Impact Ionization models

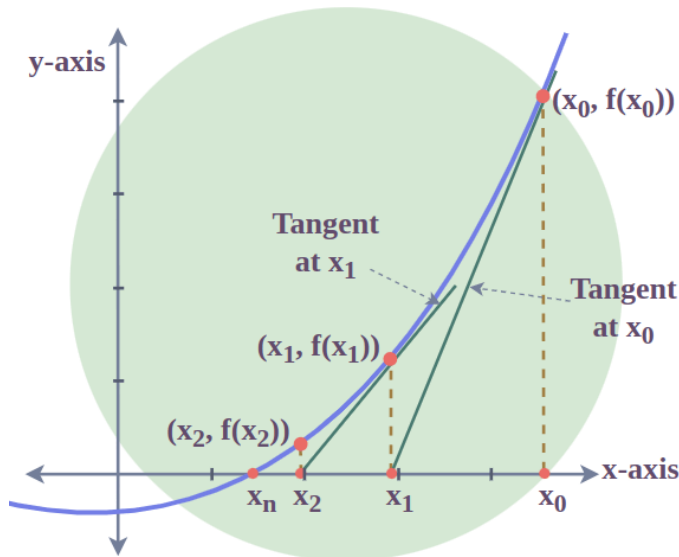
### 6. Tunneling models



# Numerical methods for solving the simulation

## Newton-Raphson (mostly used)

You need an initial guess, generally taken at equilibrium condition



Other two methods: Gummel and Block (Used for specific kind of simulations)

$$x_n = x_{n-1} - f(x_{n-1})/f'(x_{n-1})$$

Where,

- $x_{n-1}$  is the estimated  $(n-1)^{th}$  root of the function,
- $f(x_{n-1})$  is the value of the equation at  $(n-1)^{th}$  estimated root, and
- $f'(x_{n-1})$  is the value of the first order derivative of the equation or function at  $x_{n-1}$ .



# Different Kind of solutions

- **DC** : Where the applied bias is constant (Amplitude) and frequency is 0 with respect to time
- **AC** : Where the applied bias has a constant amplitude and frequency with respect to time
  - Single frequency (Change of voltage/amplitude)
  - Frequency response (Constant voltage/amplitude)
- **Transient**: The applied bias changes with respect to time

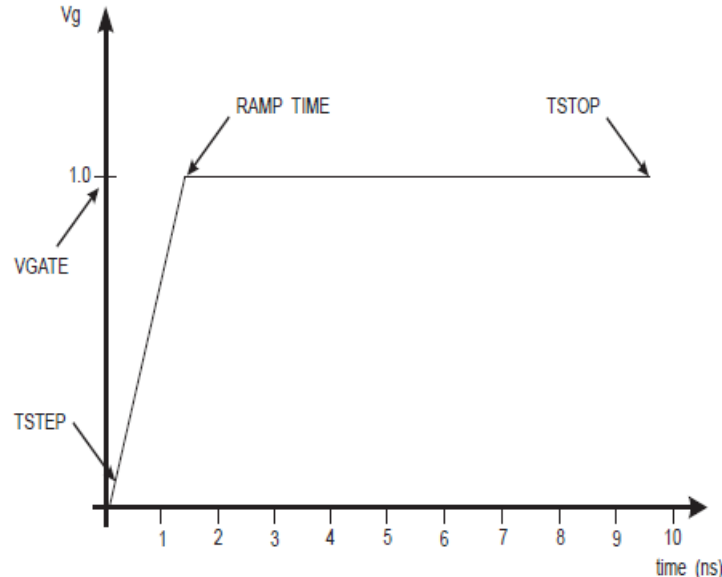
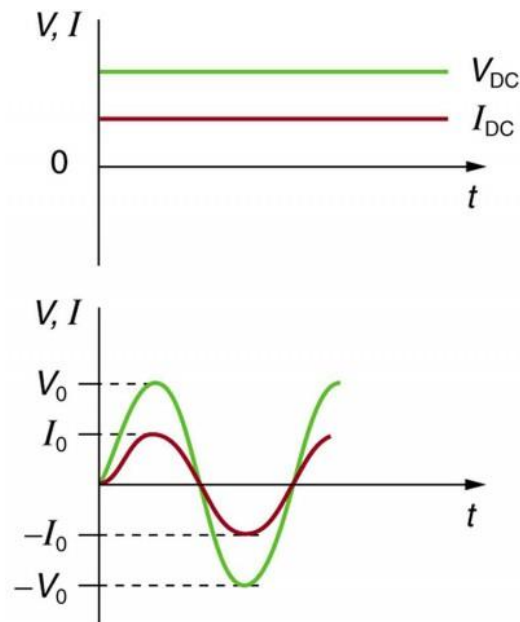


Figure 2-16 Diagram showing syntax of Transient Voltage Ramp in Atlas